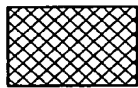
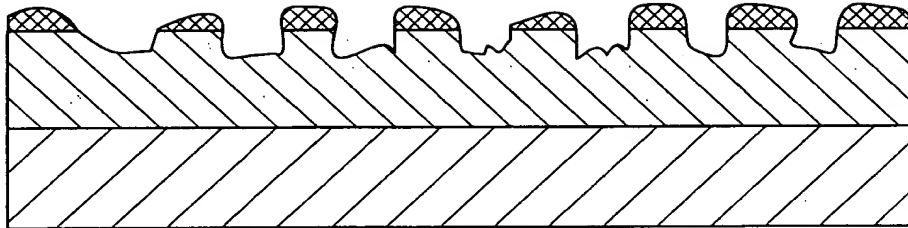


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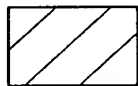
APPROVED	O.G. FIG.	
BY	CLASS	SUBCLASS
DRAFTSMAN		



PRODUCTS OF REACTION ALLOWED
TO ADHERE TO SURFACE OF FILM
WHICH MUST BE ETCHED



FILM 1 WHICH MUST BE ETCHED



FILM 2 WHICH MUST BE ETCHED

FIG.1

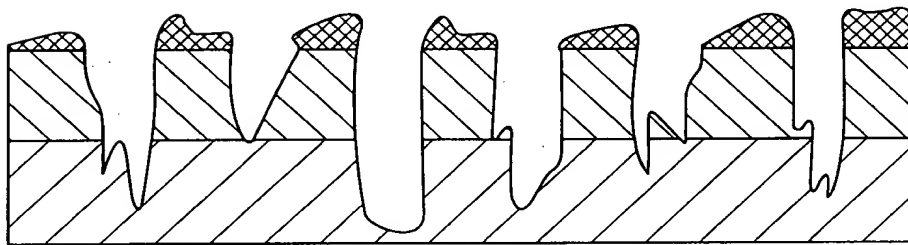
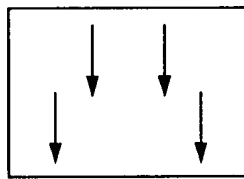
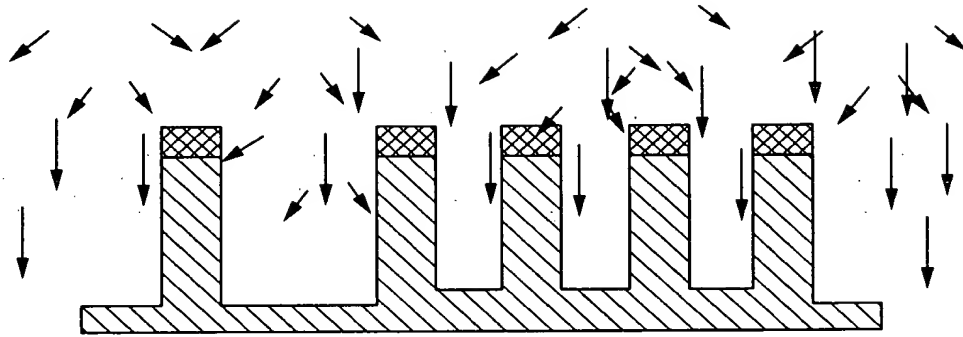
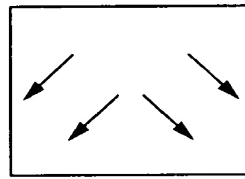


FIG.2

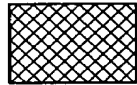
APPROVED	O.G. FIG.	
BY	CLASS	SUBCLASS
DRAFTSMAN		



IONS



RADICALS



ETCHING MASK



FILM WHICH MUST BE ETCHED

FIG.3

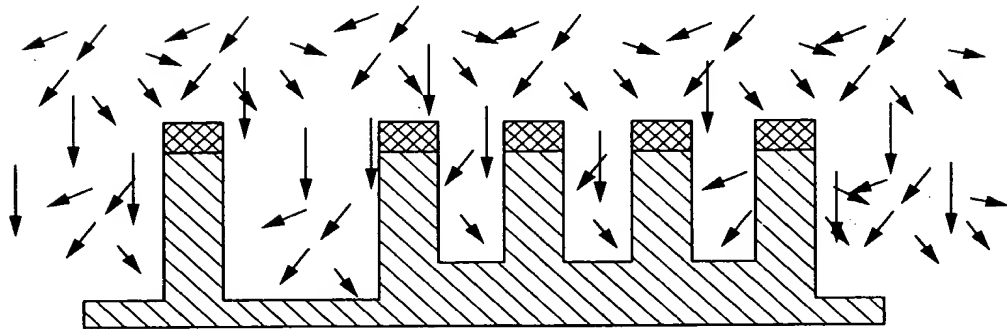


FIG.4

APPROVED	O.G. FIG.	
BY	CLASS	SUBCLASS
DRAFTSMAN		

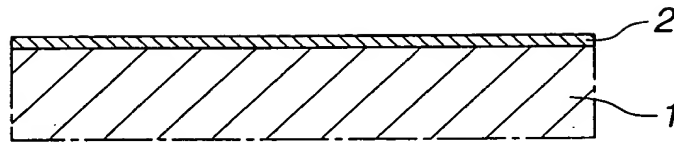


FIG.5

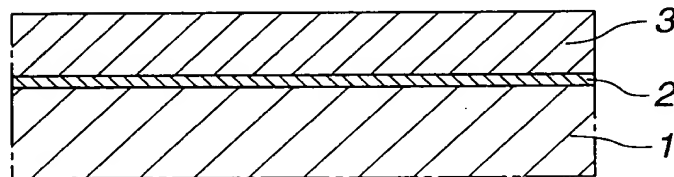


FIG.6

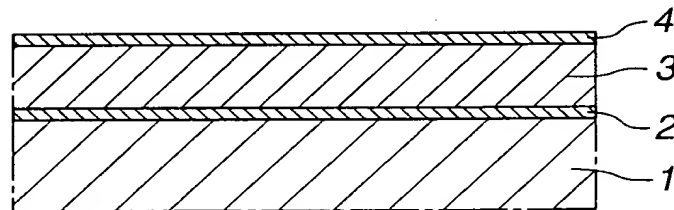


FIG.7

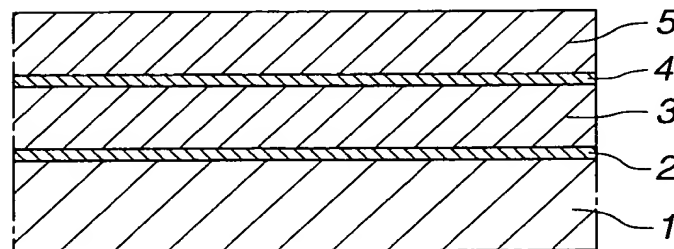


FIG.8

APPROVED	O.G. FIG.	
BY	CLASS	SUBCLASS
DRAFTSMAN		

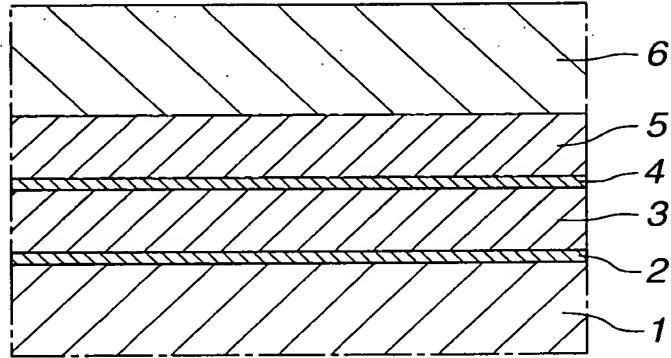


FIG.9

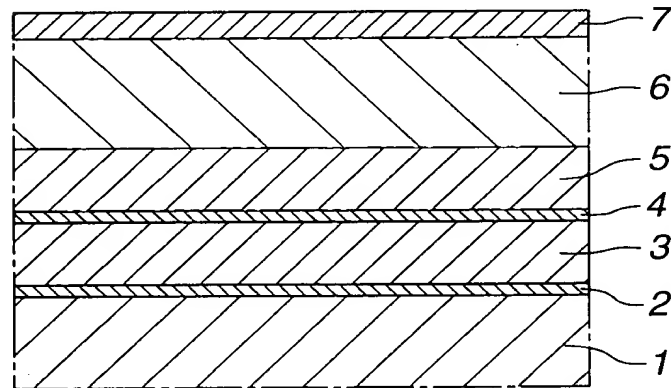


FIG.10

APPROVED	O.G. FIG.	
BY	CLASS	SUBCLASS
DRAFTSMAN		

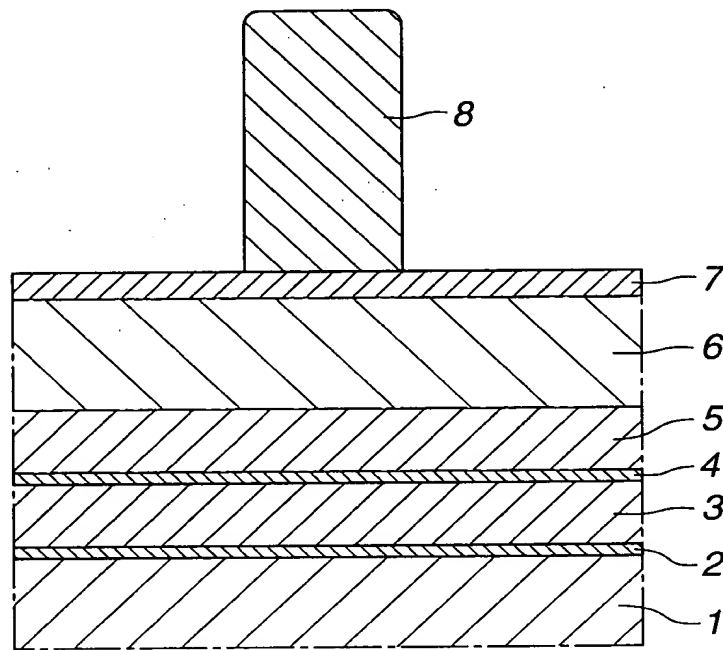


FIG.11

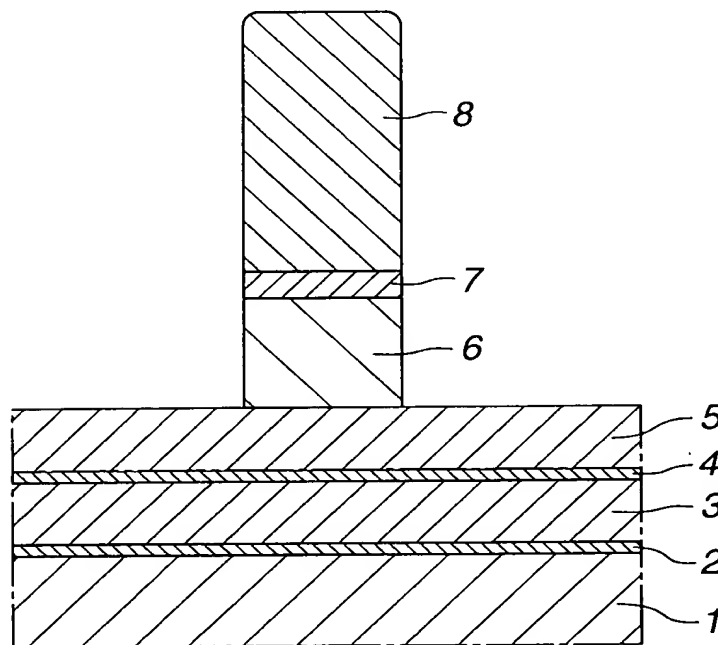


FIG.12

APPROVED	O.G. FIG.	
BY	CLASS	SUBCLASS
DRAFTSMAN		

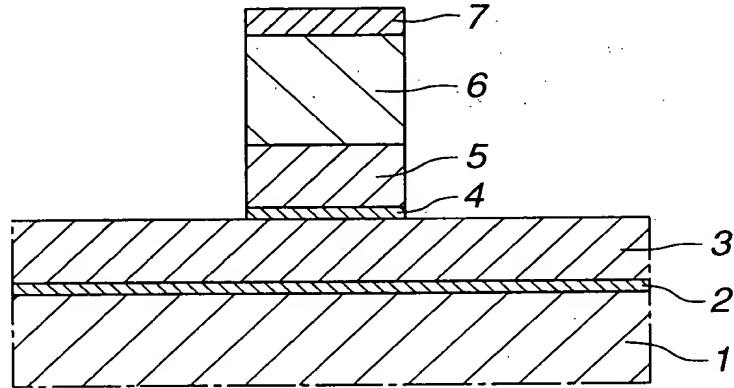


FIG.13

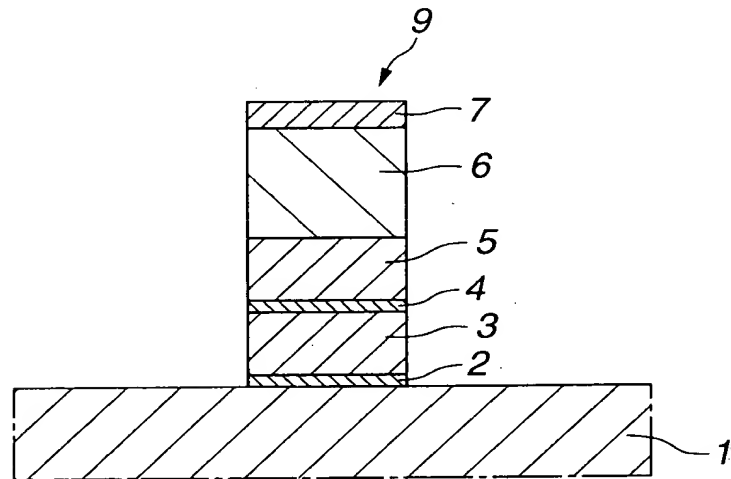


FIG.14